

TSMC-00-387



March 22, 2002

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To: Commissioner of Patents and Trademarks
Washington, D.C. 20231

Fr: George O. Saile, Reg. No. 19,572
20 McIntosh Drive
Poughkeepsie, N.Y. 12603

Subject:

Serial No. 10/056,650 01/28/02

Burn J. Lin

A MULTIPLE MASK STEP AND SCAN
ALIGNER

Grp. Art Unit: 1756

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation
In An Application.

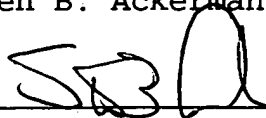
The following Patents and/or Publications are submitted to
comply with the duty of disclosure under CFR 1.97-1.99 and
37 CFR 1.56. Copies of each document is included herewith.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being
deposited with the United States Postal Service as first class
mail in an envelope addressed to: Commissioner of Patents and
Trademarks, Washington, D.C. 20231, on April 1, 2002.

Stephen B. Ackerman, Reg.# 37761

Signature/Date

 4/1/02

U.S. Patent 5,989,761 to Kawakubo et al., "Exposure Methods for Overlaying One Mask Pattern on Another," teaches a method to expose photolithographic masks onto a substrate.

U.S. Patent 5,847,813 to Hirayanagi, "Mask Holder for Microlithography Exposure," discloses a mask holding apparatus for lithographic exposure masks.

U.S. Patent 4,924,258 to Tsutsui, "Mask Holder and a Mask Conveying and Holding Mechanism Using the Same," teaches a mask holding and conveying mechanism.

Sincerely,

A handwritten signature in black ink, appearing to read 'SBA', is written over the typed name.

Stephen B. Ackerman,
Reg. No. 37761

Form PTO-1449

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

(Use several sheets if necessary)

Docket Number (Optional)

TSmc-00-387

Application Number

10 / 056, 650

Applicant

Applicant Burn J. Lin

Filing Date

Filing Date 01/28/02

Group Art Unit

Group Art Unit 1756

U. S. PATENT DOCUMENTS

[illegible]

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FOREIGN PATENT DOCUMENTS

[illegible]

OTHER DOCUMENTS (Including Author, Title, Date, Portion, Pages, Etc.)

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.